

Measurement of two-dimensional distribution of electric fields in collisional environments.

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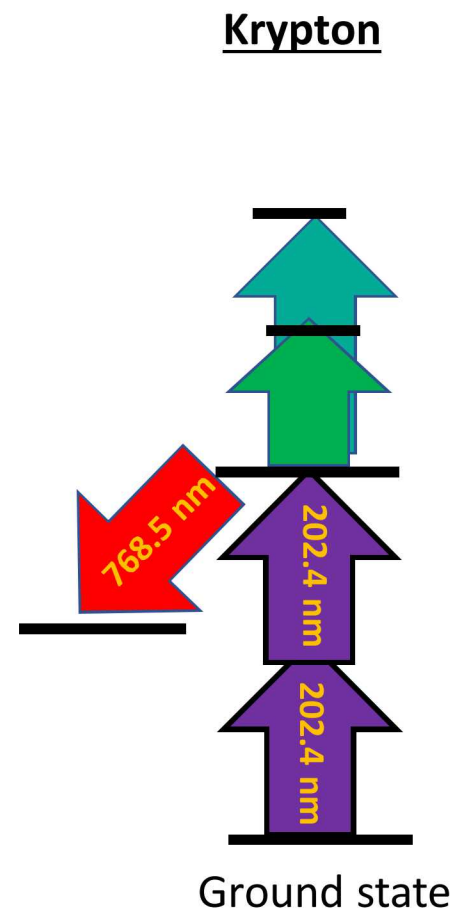
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Introduction

- In this presentation, we describe pump-probe method to measure electric fields in highly collisional environments
 - Based on laser-induced fluorescence dip (LIF-dip) spectroscopy
 - Two-photon picosecond excitation to access ground state before, during and after plasma generation
 - Tunable picosecond probe to interrogate mixing of Rydberg states before excitation relaxes
 - Monitor a depletion (dip) in the fluorescence due to redistribution of excited state



Picosecond Pump-Probe System

Picosecond pump laser

Tunable ps probe

Long-wave
pass mirror

Plasma

Imaged
LIF

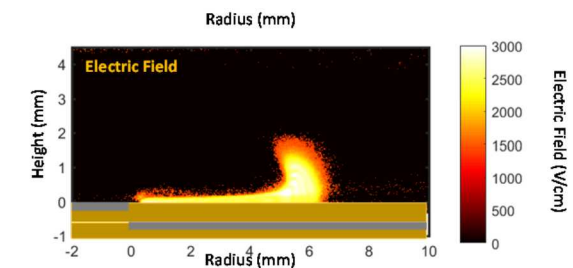
Interference
Filter

Gated
Intensified
CCD

Cylindrical
Lens

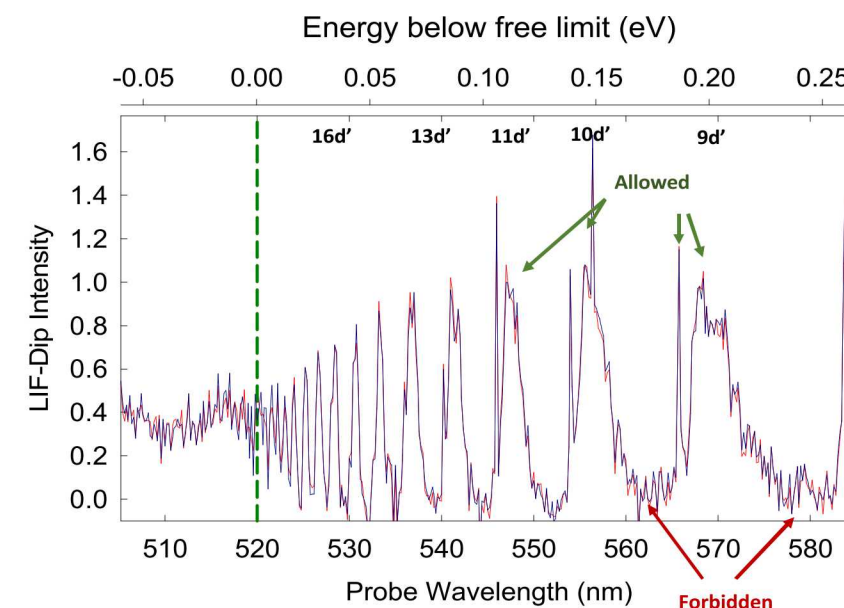
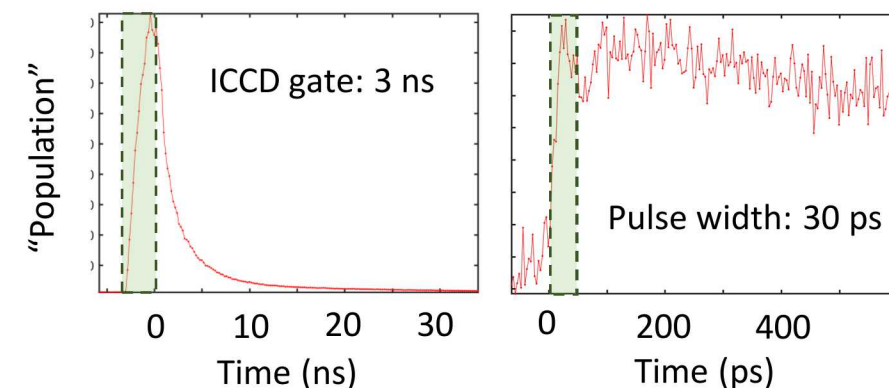
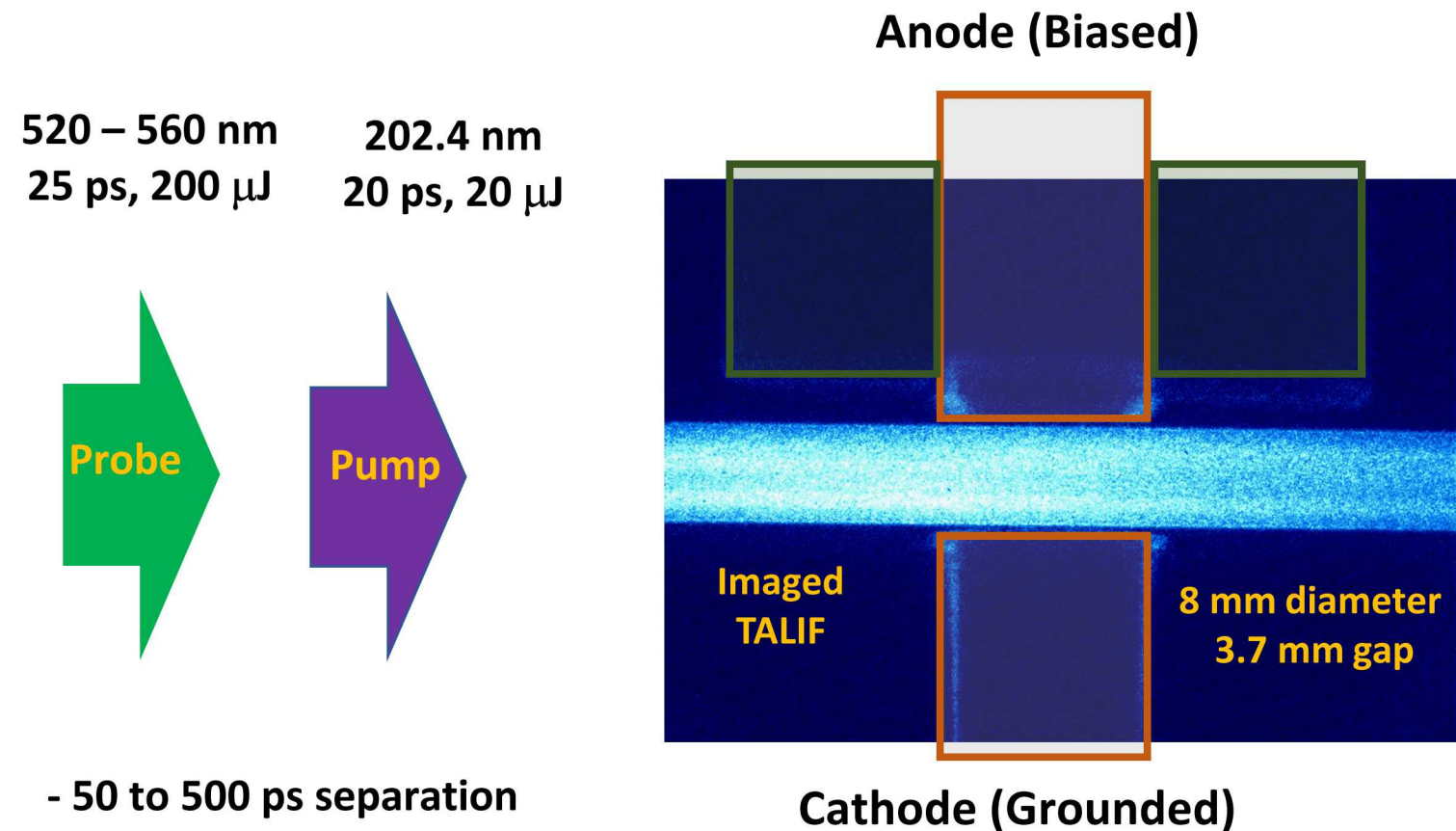
Seed laser

Seeded OPA for DUV pump



Key pieces of hardware assembled and proof of principle demonstrated

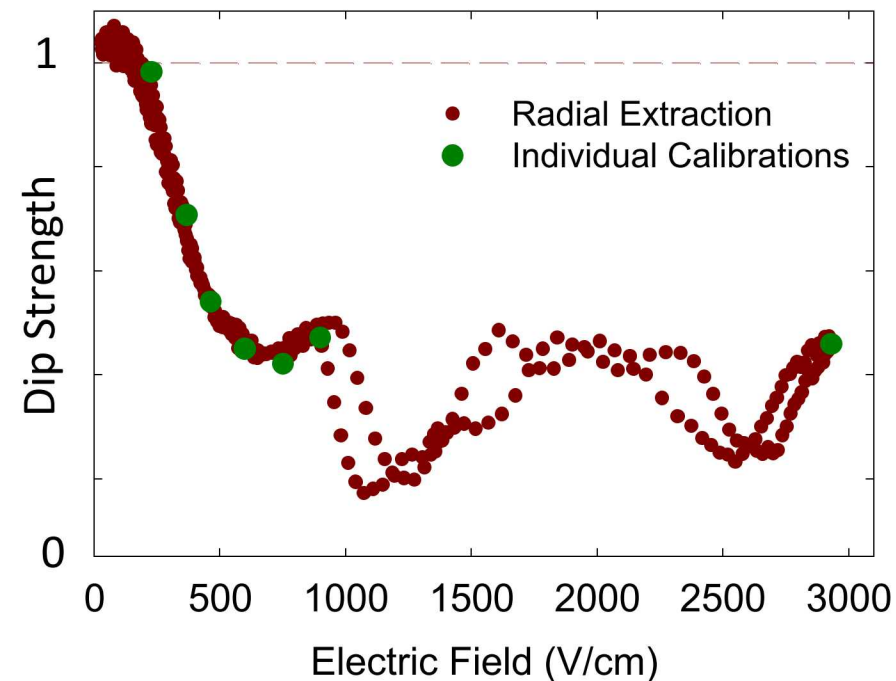
Implementation of LIF-DIP Method



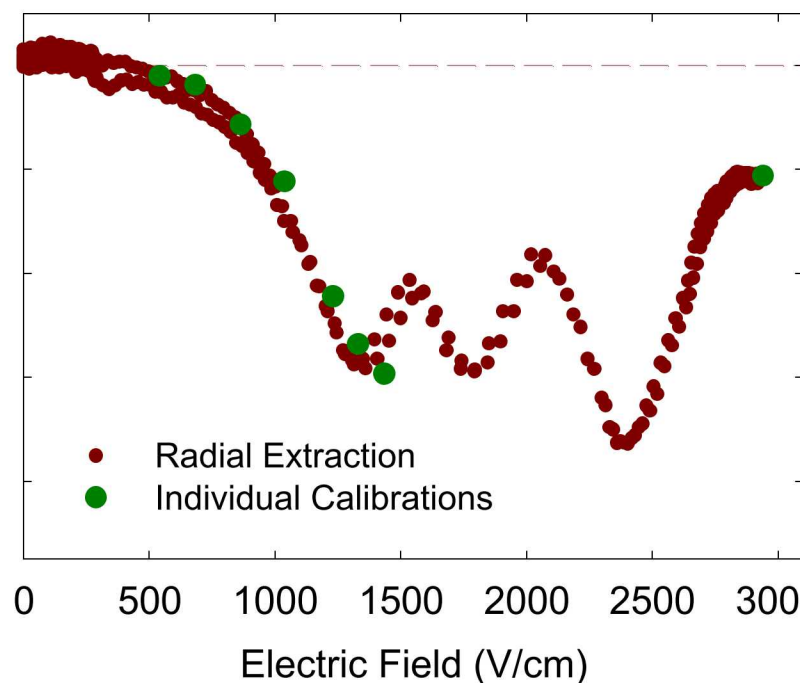
TALIF-Dip is interrogated temporally and spectrally

Representative Electric Field Calibrations

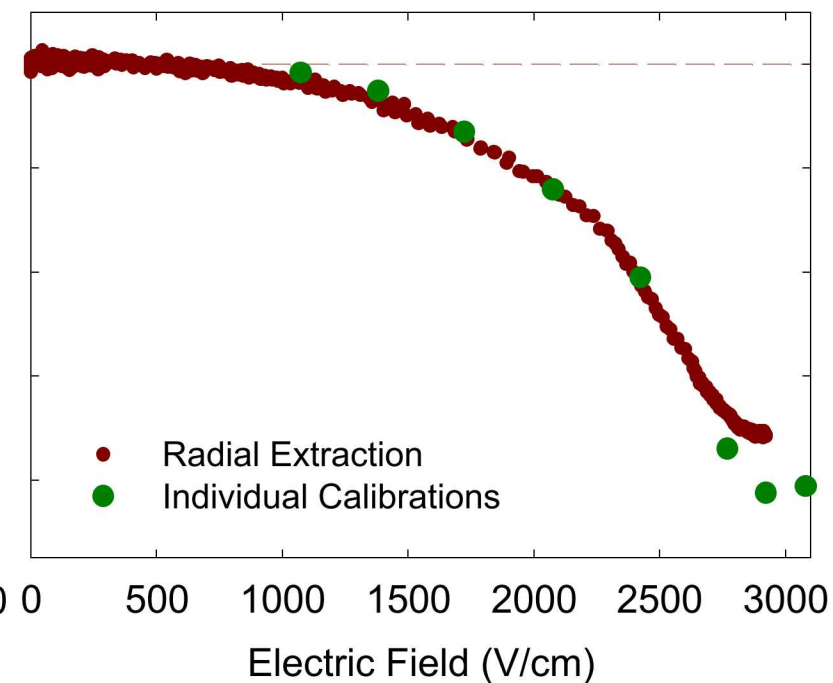
523 nm



530.4 nm



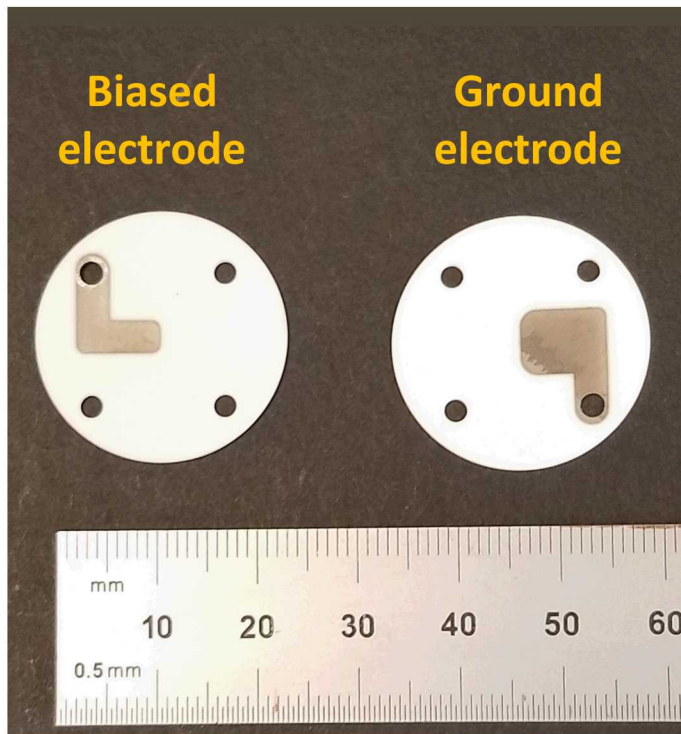
536.5 nm



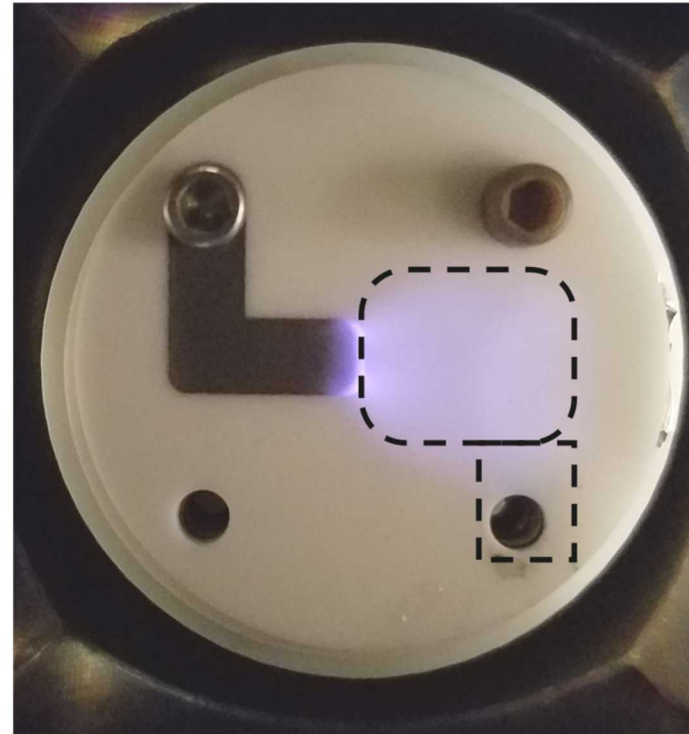
Normalized TALIF-Dip intensities are used to assess magnitude of electric fields

Surface Ionization wave Setup and Demonstration

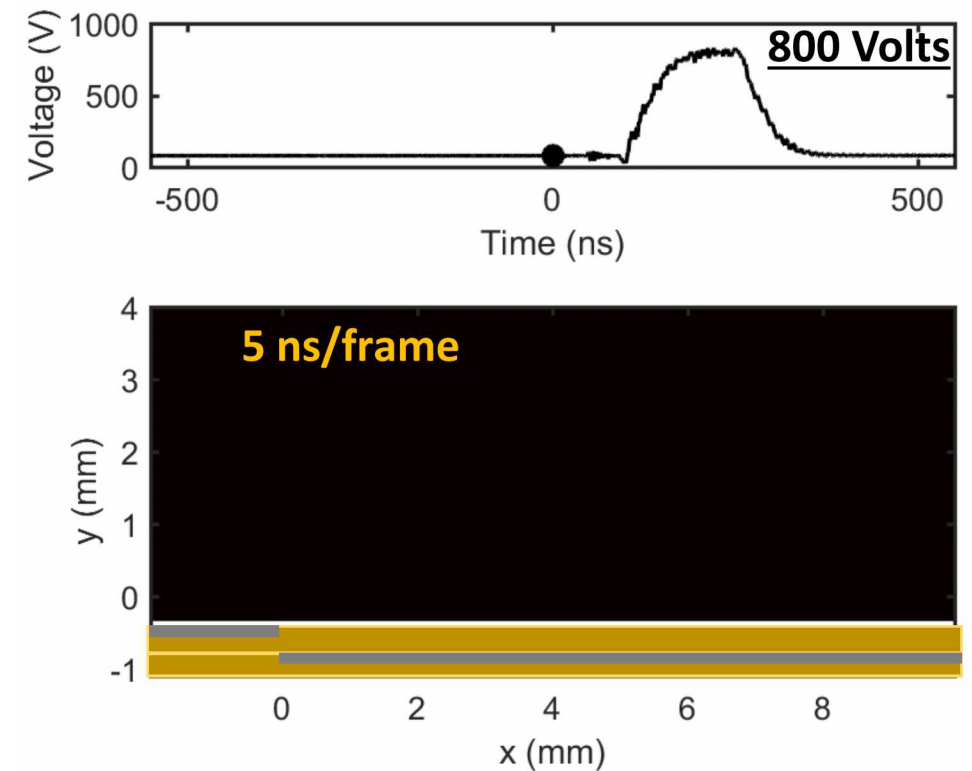
Individual electrodes



200 Torr He (5% Kr) Plasma

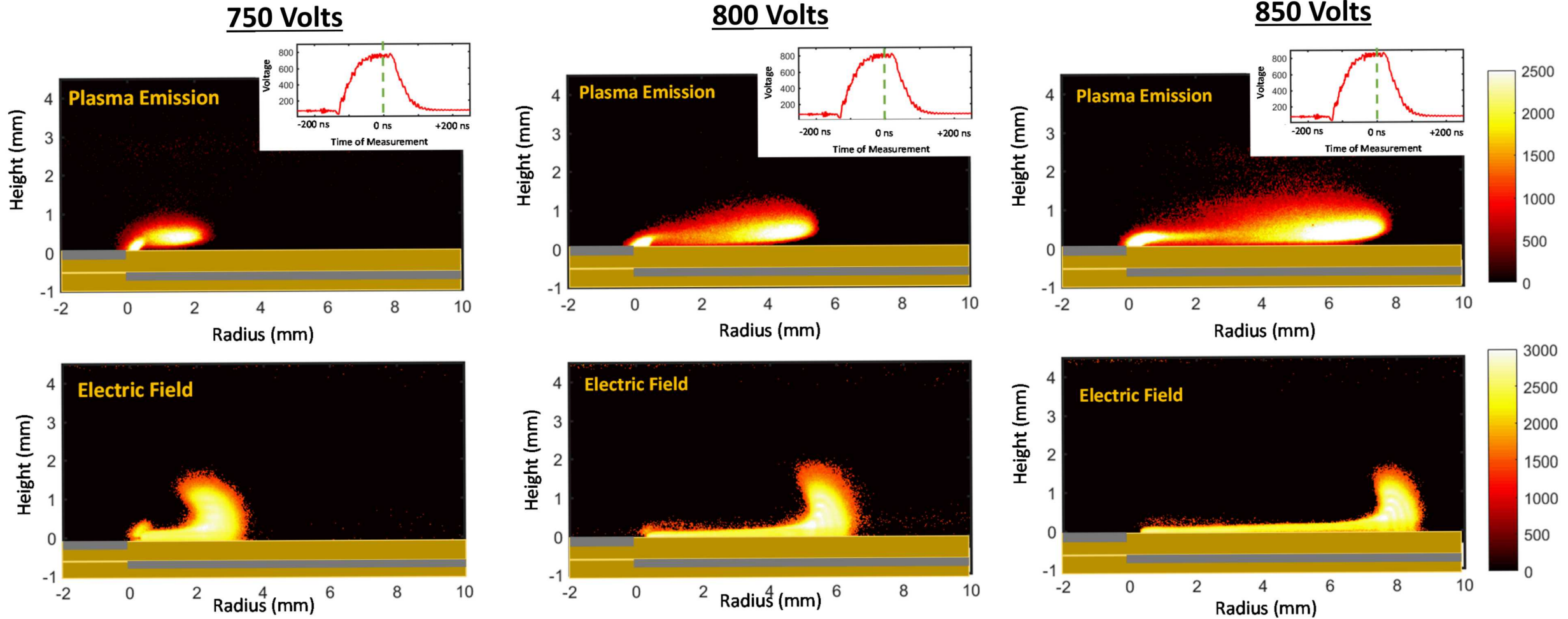


Animated Surface IW



Planar discharge is good testbed for planar TALIF and provides good access to sheaths formed at surface

Structure of Ionization Wave



Summary

- Electric Field detection has partial successes
 - Ability to spatially resolve electric fields.
 - Have good handle on lower <3 kV/cm fields
- More work needs to be done with the method
 - Ensure that technique produces unique results
 - Target and calibrate higher electric fields

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Auxiliary

Title Bar	
Slide (1): Introduction	Slide (2): Setup – discussion of ps-ps pump-probe, laser generation, timing
Slide (3): Calibration setup	Slide (4): Key Calibration trends
<div><div><div><div>~ 30 ps separation</div><div>Probe</div><div>152 femtosecond - 500 nm</div><div>For LIF dip</div></div><div><div>Pump</div><div>200 femtosecond - 400 nm</div><div>photon excitation</div></div></div><div><div>Anode, Voltage applied</div><div>Cathode grounded</div></div><div><div>Energy below free limit (eV)</div><div>1.8</div><div>1.4</div><div>1.2</div><div>1.0</div><div>0.8</div><div>0.6</div><div>0.4</div><div>0.2</div><div>0.0</div><div>LIF Dip Intensity</div><div>510</div><div>520</div><div>530</div><div>540</div><div>550</div><div>560</div><div>570</div><div>580</div><div>Probe Wavelength (nm)</div><div>530.4 nm</div><div>536.5 nm</div><div>523 nm</div><div>540 nm</div><div>550 nm</div><div>560 nm</div><div>570 nm</div><div>580 nm</div><div>530.4 nm</div><div>536.5 nm</div><div>523 nm</div><div>540 nm</div><div>550 nm</div><div>560 nm</div><div>570 nm</div><div>580 nm</div></div></div>	<div><div>523 nm</div><div>530.4 nm</div><div>536.5 nm</div></div> <div><div>Dip Strength</div><div>1</div><div>0</div><div>Electric Field (V/cm)</div><div>500</div><div>1000</div><div>1500</div><div>2000</div><div>2500</div><div>3000</div><div>500</div><div>1000</div><div>1500</div><div>2000</div><div>2500</div><div>3000</div><div>500</div><div>1000</div><div>1500</div><div>2000</div><div>2500</div><div>3000</div></div> <div><div>523 nm - 400 V/cm</div><div>530.4 nm - Field Scan</div><div>536.5 nm - Field Scan</div><div>Individual Calibrations</div><div>Expanded Fields</div><div>Field Lookup Table</div></div>